

# The Raw Silicon Wafer

## 3-inch mono crystal silicon N-type light doped wafer

Resistivity $\Omega\cdot\text{CM}$	Thickness $\mu\text{m}$	Crystal Orientation	Life $\mu\text{s}$	External Diameter $\text{mm}$	Dopant	Form				Radial inhomogene ity of resistivit y
						Line Slice	Grind	Chamferi ng Film	Position ing Piece	
5-10	200-350	<111>	>100	76.2±0.3	Phosphorus	✓	✓	✓	✓	≤20%
10-15	200-350	<111>	>100	76.2±0.3	Phosphorus	✓	✓	✓	✓	≤20%
15-20	200-350	<111>	>100	76.2±0.3	Phosphorus	✓	✓	✓	✓	≤20%
20-25	200-350	<111>	>100	76.2±0.3	Phosphorus	✓	✓	✓	✓	≤20%
25-30	200-350	<111>	>100	76.2±0.3	Phosphorus	✓	✓	✓	✓	≤20%
30-35	200-350	<111>	>100	76.2±0.3	Phosphorus	✓	✓	✓	✓	≤20%
35-40	200-350	<111>	>100	76.2±0.3	Phosphorus	✓	✓	✓	✓	≤20%
40-45	200-350	<111>	>100	76.2±0.3	Phosphorus	✓	✓	✓	✓	≤20%
45-50	200-350	<111>	>100	76.2±0.3	Phosphorus	✓	✓	✓	✓	≤20%
50-55	200-350	<111>	>100	76.2±0.3	Phosphorus	✓	✓	✓	✓	≤20%

## 4-inch mono crystal silicon N-type light doped wafer

Resistivity $\Omega\cdot\text{CM}$	Thickness $\mu\text{m}$	Crystal Orientation	Life $\mu\text{s}$	External Diameter $\text{mm}$	Dopant	Form				Radial inhomogene ity of resistivit y
						Line Slice	Grind	Chamferi ng Film	Position ing Piece	
5-10	200-350	<111>	>100	101.6±0.3	Phosphorus	✓	✓	✓	✓	≤20%
10-15	200-350	<111>	>100	101.6±0.3	Phosphorus	✓	✓	✓	✓	≤20%
15-20	200-350	<111>	>100	101.6±0.3	Phosphorus	✓	✓	✓	✓	≤20%
20-25	200-350	<111>	>100	101.6±0.3	Phosphorus	✓	✓	✓	✓	≤20%
25-30	200-350	<111>	>100	101.6±0.3	Phosphorus	✓	✓	✓	✓	≤20%
30-35	200-350	<111>	>100	101.6±0.3	Phosphorus	✓	✓	✓	✓	≤20%
35-40	200-350	<111>	>100	101.6±0.3	Phosphorus	✓	✓	✓	✓	≤20%
40-45	200-350	<111>	>100	101.6±0.3	Phosphorus	✓	✓	✓	✓	≤20%
45-50	200-350	<111>	>100	101.6±0.3	Phosphorus	✓	✓	✓	✓	≤20%
50-55	200-350	<111>	>100	101.6±0.3	Phosphorus	✓	✓	✓	✓	≤20%

## 3-inch mono crystal silicon heavy doped wafer

Resistivity $\Omega\cdot\text{CM}$	Thicknes $\mu\text{m}$	Crystal Orientation	Model	External Diameter $\text{mm}$	Dopant	Form				Radial inhomogene ity of resistivit y
						Line Slice	Grind	Chamferi ng Film	Position ing Piece	
0.003-0.005	200-350	<111>	N/P	76.2±0.3	Phosphorus /Boron	/	✓	✓	✓	/
0.005-0.008	200-350	<111>	N/P	76.2±0.3	Phosphorus /Boron	/	✓	✓	✓	/
0.02-0.03	200-350	<111>	N/P	76.2±0.3	Phosphorus /Boron	/	✓	✓	✓	/

## 4 inch monocrystal silicon heavy doped wafer

						Form				Radial
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